

**REMARKS**

Claims 1-23 were examined and reported in the Office Action. Claims 1, 2, 8, 14 and 15 are rejected. Claims 1, 3, 14 and 16 are amended. Claims 1-23 remain.

Applicant requests reconsideration of the application in view of the following remarks.

**I. 35 U.S.C. § 103**

A. It is asserted in the Office Action that claims 1, 2, and 8 are rejected in the Office Action under 35 U.S.C. § 103(a), as being unpatentable over U. S. Patent 6,599,821 issued to Lee ("Lee") in view of U. S. Patent 6,455,383 issued to Wu ("Wu") and U. S. Patent 5,308,655 issued to Eichman et al ("Eichman"). Applicant respectfully traverses the aforementioned rejection for the following reasons.

According to MPEP §2142

[t]o establish a prima facie case of obviousness, three basic criteria must be met. First, there must be some suggestion or motivation, either in the references themselves or in the knowledge generally available to one of ordinary skill in the art, to modify the reference or to combine reference teachings. Second, there must be a reasonable expectation of success. Finally, the prior art reference (or references when combined) must teach or suggest all the claim limitations. The teaching or suggestion to make the claimed combination and the reasonable expectation of success must both be found in the prior art, and not based on applicant's disclosure. (In re Vaeck, 947 F.2d 488, 20 USPQ2d 1438 (Fed. Cir. 1991)).

Applicant's amended claim 1 contains the limitations of

[a] method for fabricating a semiconductor device, comprising the steps of: a) forming a stack layer of a gate layer, a poly-silicon layer, a tungsten layer, and a hard mask sequentially deposited on a semiconductor substrate; b) carrying out a selective oxidation process adopting a rapid thermal process (RTP), wherein the poly-silicon layer of the stack layer is only oxidized; c) performing a heat treatment process in a vacuum ambient of a low pressure chemical vapor deposition (LPCVD)

furnace for releasing a stress caused by the RTP; and d) carrying out a process for forming a gate sealing nitride layer on the heat treated stack layer.

Lee discloses a method for fabricating a conductive line pattern that uses a heat treatment process for releasing a stress caused by a RTP. In Lee, the RTP is performed in a predetermined gas ambient for forming an oxide or a nitride film. In Applicant's claimed invention, however, a heat treatment after a RTP for oxidizing a poly-silicon layer or a LPCVD for oxidizing a gate sealing nitride layer is performed in a vacuum ambient of a low pressure chemical vapor deposition (LPCVD) furnace for releasing a stress caused by the RTP or the LPCVD.

Therefore, it is readily seen that Lee does not teach, disclose or suggest "b) carrying out a selective oxidation process adopting a rapid thermal process (RTP), wherein the poly-silicon layer of the stack layer is only oxidized; c) performing a heat treatment process in a vacuum ambient of a low pressure chemical vapor deposition (LPCVD) furnace for releasing a stress caused by the RTP."

Wu discloses methods of fabricating scaled MOSFETS. Wu, however, does not disclose, teach or suggest a heat treatment process for releasing a stress caused by a RTP. In Wu, the heat treatment, e.g., LPCVD, is performed in a predetermined gas ambient for forming an oxide or a nitride film. In Applicant's claimed invention, however, a heat treatment after a RTP for oxidizing a poly-silicon layer or a LPCVD for oxidizing a gate sealing nitride layer is performed in a vacuum ambient of a low pressure chemical vapor deposition (LPCVD) furnace for releasing a stress caused by the RTP or the LPCVD.

Therefore, it is readily seen that Wu does not teach, disclose or suggest "b) carrying out a selective oxidation process adopting a rapid thermal process (RTP), wherein the poly-silicon layer of the stack layer is only oxidized; c) performing a heat treatment process in a vacuum ambient of a low pressure chemical vapor deposition (LPCVD) furnace for releasing a stress caused by the RTP."

Eichman discloses a method for forming low resistivity TiN film using TiCl<sub>4</sub> and NH<sub>3</sub> gases by LPCVD under in-situ or under ex-situ. That is, Eichman is concerned with the point that after the TiCl<sub>4</sub> gas flows into the LPCVD chamber, the

NH<sub>3</sub> gas flows into the LPCVD chamber for stripping off the remaining unbound chlorine within the TiN film, which may be performed in the same LPCVD chamber or in the other LPCVD chamber. In Eichman, the heat treatment, e.g., LPCVD, is performed in a predetermined gas ambient for forming an oxide or a nitride film. In Applicant's claimed invention, however, a heat treatment after a RTP for oxidizing a poly-silicon layer or a LPCVD for oxidizing a gate sealing nitride layer is performed in a vacuum ambient of a low pressure chemical vapor deposition (LPCVD) furnace for releasing a stress caused by the RTP or the LPCVD.

Therefore, it is readily seen that Eichman does not teach, disclose or suggest "b) carrying out a selective oxidation process adopting a rapid thermal process (RTP), wherein the poly-silicon layer of the stack layer is only oxidized; c) performing a heat treatment process in a vacuum ambient of a low pressure chemical vapor deposition (LPCVD) furnace for releasing a stress caused by the RTP."

Since neither Lee, Wu, Eichman, and therefore, nor the combination of the three teach, disclose or suggest all the limitations of Applicant's amended claim 1, as listed above, Applicant's amended claim 1 is not obvious over Lee in view of Wu, and further in view of Eichman since a *prima facie* case of obviousness has not been met under MPEP §2142. Additionally, the claims that directly or indirectly depend from amended claim 1, namely claims 2 and 8, would also not be obvious over Lee in view of Wu and further in view of Eichman for the same reason.

Accordingly, withdrawal of the 35 U.S.C. § 103(a) rejections for claims 1, 2, and 8 are respectfully requested.

**B.** It is asserted in the Office Action that claims 14 and 15 are rejected in the Office Action under 35 U.S.C. § 103(a), as being unpatentable over Wu in view of Eichman. Applicant respectfully traverses the aforementioned rejection for the following reasons.

Applicant's amended claim 14 contains the limitations of

[a] method for fabricating a semiconductor device, comprising the steps of: a3) forming a stack layer of a gate oxide layer, a poly-silicon layer, a tungsten layer,

and a hard mask sequentially deposited on a semiconductor substrate; b3) carrying out a selective oxidation process, wherein the poly-silicon layer of the stack layer is only oxidized; c3) depositing a gate sealing nitride layer on the stack layer selectively oxidized by low pressure chemical vapor deposition (LPCVD); d3) performing a heat treatment process in a vacuum or inert gas ambient of an LPCVD furnace or an annealing furnace for releasing a stress exerted during the selective oxidation process and gate sealing nitride layer deposition process; and e) performing a rapid thermal process (RTP) for activating source/drain regions of the semiconductor device.

Wu and Eichman are addressed above in section I(A) regarding Applicant's amended claim 1. Similar to amended claim 1, Applicant's claim 14 contains the limitations of "performing a heat treatment process in a vacuum or inert gas ambient of an LPCVD furnace or an annealing furnace for releasing a stress exerted during the selective oxidation process and gate sealing nitride layer deposition process; and e) performing a rapid thermal process (RTP) for activating source/drain regions of the semiconductor device."

In either Eichman or Wu, the heat treatment, e.g., LPCVD, or RTP is performed in a predetermined gas ambient for forming an oxide or a nitride film. In Applicant's claimed invention, however, a heat treatment after a RTP for oxidizing a poly-silicon layer or a LPCVD for oxidizing a gate sealing nitride layer is performed in a vacuum or inert ambient of a low pressure chemical vapor deposition (LPCVD) furnace for releasing a stress caused by the RTP or the LPCVD.

Since neither Wu, Eichman, and therefore, nor the combination of the two teach, disclose or suggest all the limitations of Applicant's amended claim 14, as listed above, Applicant's amended claim 14 is not obvious over Wu in view of Eichman since a *prima facie* case of obviousness has not been met under MPEP §2142. Additionally, the claim that directly depends from amended claim 14, namely claim 15, would also not be obvious over Wu in view of Eichman for the same reason.

Accordingly, withdrawal of the 35 U.S.C. § 103(a) rejections for claims 14 and 15 are respectfully requested.

**II. Allowable Subject Matter**

Applicant notes with appreciation the Examiner's assertion that claims 3-7, 9-13 and 16-23 are objected to as being dependent upon a rejected base claim, but would be allowable if rewritten in independent form including all of the limitations of the base claim and any intervening claims.

Applicant respectfully asserts that claims 1-23, as they now stand, are allowable for the reasons given above.



### CONCLUSION

In view of the foregoing, it is submitted that claims 1-23 patentably define the subject invention over the cited references of record, and are in condition for allowance and such action is earnestly solicited at the earliest possible date. If the Examiner believes a telephone conference would be useful in moving the case forward, he is encouraged to contact the undersigned at (310) 207-3800.

If necessary, the Commissioner is hereby authorized in this, concurrent and future replies, to charge payment or credit any overpayment to Deposit Account No. 02-2666 for any additional fees required under 37 C.F.R. §§1.16 or 1.17, particularly, extension of time fees.

Respectfully submitted,

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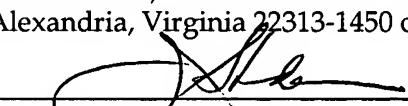
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### CERTIFICATE OF MAILING

I hereby certify that this correspondence is being deposited with the United States Postal Service as First Class Mail with sufficient postage in an envelope addressed to: Mail Stop Amendment, Commissioner for Patents, P. O. Box 1450, Alexandria, Virginia 22313-1450 on October 26, 2005.

  
Jean Svoboda